For at least the above reasons, it is submitted that none of the claims are either anticipated or rendered obvious by these cited references. Withdrawal of the rejections is requested.

For at least the above reasons, it is submitted that the application is in condition for allowance. Prompt consideration and allowance are solicited.

Attached hereto is a marked-up version of the changes made to the claims by the current amendment. The attached page is captioned **"Version With Markings To Show Changes Made."**

The Office is authorized to charge any fees required under 35 U.S.C. § 1.16 and 1.17, and fees for a petition for an extension of time under 37 C.F.R. §1.136, to Deposit Account 11-0600.

Should there be any questions concerning this matter, the Examiner is invited to contact Applicants' undersigned attorney.

Respectfully submitted,

Dated: May 29, 2003

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VERSION OF AMENDED CLAIMS MARKED UP TO SHOW CHANGES

IN THE CLAIMS

Please amend claim 1 as follows:

1. (Twice Amended) An electron beam [lithograph] lithography system comprising:

exposure map creating means which, based on positional relations between meshes dividing a region to be rendered by an electron beam on the one hand and shots to be rendered by said electron beam on the other hand, creates an exposure map by calculating an area density from a shot area included in each of said meshes; and

proximity effect correcting means for correcting a level of exposure for each of said shots by referencing said exposure map so that each shot is exposed at the corrected level;

wherein said exposure map creating means includes judging means for judging whether or not each shot straddles a plurality of meshes by using a plurality of memories and adding circuits;

said judging means judges whether the shot in question straddles said plurality of meshes based on positional relations between coordinates of two diagonally positioned edge points of each shot on the one hand and mesh boundaries on the other hand, and

said exposure map creating means divides each shot straddling said plurality of meshes by boundaries of said meshes so that either area values or area densities of divided slots included in each mesh are stored in each plurality of memories respectively and are added to the mesh in question by calculating in said adding circuits, respectively.